

<b>Notice of References Cited</b>	Application/Control No. 09/851,313		Applicant(s)/Patent Under Reexamination USAMI, TATSUYA	
	Examiner Julio J. Maldonado		Art Unit 2823	Page 1 of 1

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*	U	Wolf et al., Silicon Processing for the VLSI Era, Volume 1-Process Technology, 1986, Lattice Press, pages 168-174.
*	V	Chen et al., Effects of slurry formulations on chemical-mechanical polishing of low dielectric constant polysiloxanes: hydrido-organo siloxane and methyl silsesquioxane; J. Vac. Sci Technol. B 18(1), Jan/Feb 2000; pages 201-207
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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